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PN - JP2002134455 A 20020510
PD - 2002-05-10
PR - JP20000324224 20001024
OPD - 2000-10-24
TI - SUBSTRATE TREATMENT DEVICE
IN - YAMAMOTO HIROSHI
PA - DAINIPPON SCREEN MFG
IC - H01L21/304

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TI - Substrate processing apparatus for flat panel display, liquid crystal display, has ozonizer to supply ozone to nozzle containing ozone water supplied by ozone water supply pipe
PR - JP20000324224 20001024
PN - JP2002134455 A 20020510 DW 200248 H01L21/304 008pp
PA - (DNIS) DAINIPPON SCREEN SEIZO KK
IC - H01L21/304
AB - JP2002134455 NOVELTY - A nozzle (12) discharges ozone water (17) from a source through a supply pipe (14), onto a substrate (11) supported by a spin chuck (10). An ozonizer supplies ozone (18) to the ozone water in the nozzle.
 - USE - For processing semiconductor wafer used for semiconductor devices, flat panel displays, liquid crystal displays requiring processing of glass substrates by cleaning the substrates from organic substances like resist membrane.
 - ADVANTAGE - By having a separate ozone source and ozone supply pipe, ozone of sufficient and high concentration is supplied to the substrate, which aids in removing the organic substances from the substrate by the oxidation of ozone.
 - DESCRIPTION OF DRAWING(S) - The figure shows a side view of a substrate processing apparatus.
 - Spin chuck 10
 - Substrate 11
 - Nozzle 12
 - Supply pipe 14
 - Ozone water 17
 - Ozone 18
 - (Dwg. 1/5)

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IN - YAMAMOTO HIROSHI
PA - DAINIPPON SCREEN MFG CO LTD
TI - SUBSTRATE TREATMENT DEVICE
AB - PROBLEM TO BE SOLVED: To provide a substrate treatment device which can supply a treatment

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liquid with a sufficient ozone concentration to a substrate.

- SOLUTION: This substrate treatment device, which supplies ozone water to a substrate 11 for treating the substrate 11, has a spin chuck 10 which supports the substrate 11, a nozzle from which the ozone water (a treatment liquid) is spouted out against the substrate 11 supported by the spin chuck 10, an ozone water supply piping 14, through which the ozone water is supplied to the nozzle, and an ozone supply piping 16 through which ozone is supplied into the ozone water 17 supplied to the nozzle.

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